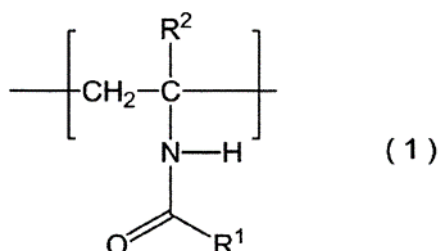


ABSTRACT OF THE DISCLOSURE

To provide a means capable of sufficiently removing organic residues present on the surface of a polishing object after polishing containing silicon oxide or polysilicon.

A surface treatment composition contains a polymer having a constituent unit represented by Formula (1) below and water and is used for treating the surface of a polishing object after polishing,



in which, in Formula (1) above, R¹ is a hydrocarbon group having 1 to 5 carbon atoms and R² is a hydrogen atom or a hydrocarbon group having 1 to 3 carbon atoms.